

1752



**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

7/9

In re application of

Docket No: Q62650

Toshiaki AOAI, et al.

Appln. No.: 09/759,362

Group Art Unit: 1752

Confirmation No.: 1920

Examiner: J. CHU

Filed: January 16, 2001

For: ELECTRON BEAM OR X-RAY NEGATIVE-WORKING RESIST COMPOSITION

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**AMENDMENT UNDER 37 C.F.R. § 1.111**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

This Amendment is in response to the Office Action dated August 30, 2002, in which the Examiner set forth a three-month period for response, making a response timely if filed on or before December 2, 2002 (November 30, 2002 being a Saturday).

Please amend the above-identified application as follows:

**IN THE CLAIMS:**

**Please cancel claims 3 and 10 without prejudice or disclaimer.**

**Please enter the following amended claims 1 and 9:**

1 (amended). A negative-working resist composition for electron beams or X-rays comprising (A) a compound generating an acid and/or radical species by the irradiation of electron beams or X-rays, (B) a resin which is insoluble in water and

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